Attorney Docket: BHT/3230-56

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant

YEH

Application No.

10/601,701

OCT 2 0 2003

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June 24, 2003

Title

METHOD FOR FABRICATION OF POLYCRYSTALLIN

SILICON THIN FILM TRANSISTORS

Group Art Unit

2812

Examiner

Unknown

Docket No.

BHT/3230-56

MAIL STOP OFFICE OF INITIAL PATENT EXAMINATION

:

:

Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

TRANSMITTAL COVER SHEET

Sir:

Transmitted herewith for filing are the following:

- 1. INFORMATION DISCLOSURE STATEMENT.
- 2. Form PTO-1449 (in duplicate), along with copies of nine (9) references cited therein.

The Commissioner is hereby authorized to charge any fees which may be required for the filing of this document to **Deposit Account No. 501874**.

Respectfully submitted,

Date: October 20, 2003

Ву:

Bruce H. Troxell Reg. No. 26,592

TROXELL LAW OFFICE PLLC 5205 Leesburg Pike, Suite 1404 Falls Church, Virginia 22041 Telephone: (703) 575-2711 Telefax: (703) 575-2707

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Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 CFR 1.56, and 37 CFR 1.97-1.98, the documents listed on the attached form PTO-1449 are hereby made of record in this patent application. Copies of the listed documents are enclosed.

As this Information Disclosure Statement is being filed prior to the mailing of the first Official Action in this application, no fee is believed due in order to have the enclosed references considered by the Examiner and made of record in the application.

Early action on the merits of the application is earnestly solicited.

By:

Respectfully submitted,

Date: <u>October 20, 2003</u>

Bruce H. Troxell

Reg. No. 26,592

TROXELL LAW OFFICE PLLC 5205 Leesburg Pike, Suite 1404 Falls Church, Virginia 22041 Telephone: (703) 575-2711

Telefax: (703) 575-2707

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FORM PTO 1449 (modified)			ATTY DOCKET NO. BHT/3230-56 APPLICATION NO. 10/601,701				
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			APPLICANT YEH				
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)			FILING DATE Jun 24, 2003		GROUP 281 :	GROUP 2812	
Date Submitted to PTO: Octob r 20, 2003				· · · · · · · · · · · · · · · · · · ·			
U.S. PATENT DOCUMENTS							
ONTIAL E	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
OCT 2 0 2003 4	4,330,363	05/18/82	Biegesen et al.				
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& TRADEMARK	5,021,119	06/04/91	Fan et al.				
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	6,495,405 B2	12/17/02	Voutsas et al.				
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT	
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
	Recessed-Chan	High-Performance Low-Temperature Poly-Si TFTs Crystallized by Excimer Laser with Recessed-Channel Structure, Lin et al., IEEE Electron Device Letters, Vol. 22, No. 6, June 2001, pages 269-271					
	Prepatterned La	Performance Improvement Obtained for Thin-Fil Transistors Fabricated in Prepatterned Laser-Recrystallized Polysilicon, Giust et al., IEEE Electron Device Letters, Vol. 18, No. 6, June 1997, pages 296-298					
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		High-Performance Single Crystalline-Silicon TFTs on a Non-Alkali Glass Substrate, Sano et al. Fujitsu Laboratories Ltd., Atsugi 243-0197, Japan (C) 2002 IEEE					
EXAMINER			DATE CONSIDI	DATE CONSIDERED			

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.